

CAVITY LIMITATIONS

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Outline

- Residual resistance
- Multipacting
- Field emission
- Quench
- High-field Q-slope





The Real World









Losses in SRF Cavities

• Different loss mechanism are associated with different regions of the cavity surface









Origin of Residual Surface Resistance

- Dielectric surface contaminants (gases, chemical residues, dust, adsorbates)
- Normal conducting defects, inclusions
- Surface imperfections (cracks, scratches, delaminations)
- Trapped magnetic flux
- Hydride precipitation
- Localized electron states in the oxide (photon absorption)

R_{res} is typically 5-10 $n\Omega$ at 1-1.5 GHz





Trapped Magnetic Field



- Vortices are normal to the surface
- 100% flux trapping
- RF dissipation is due to the normal conducting core, of resistance R_n

$$R_{res} \cong R_n \frac{H_i}{H_{c2}}$$

H_i = residual DC magnetic field

- For Nb: $R_{res} \approx 0.3$ to Ω/mG around 1 GHz Depends on material treatment
- While a cavity goes through the superconducting transition, the ambient magnetic filed cannot be more than a few mG.
- The earth's magnetic shield must be effectively shielded.
- Thermoelectric currents can cause trapped magnetic field, especially in cavities made of composite materials.





Trapped Magnetic Field









R_{res} **Due to Hydrides (Q-Disease)**

- Cavities that remain at 70-150 K for several hours (or slow cool-down, < 1 K/min) experience a sharp increase of residual resistance
- More severe in cavities which have been heavily chemically etched









Hydrogen: "Q-disease"



- H is readily absorbed into Nb where the oxide layer is removed (during chemical etching or mechanical grinding)
- H has high diffusion rate in Nb, even at low temperatures.
- H precipitates to form a hydride phase with poor superconducting properties: $T_c=2.8$ K, $H_c=60$ G

- At room temperature the required concentration to form a hydride is 10³-10⁴ wppm
- At 150K it is < **10 wppm**









Cures for Q-disease

- Fast cool-down
- Maintain acid temperature below ~ 20 °C during BCP
- "Purge" H_2 with N_2 "blanket" and cover cathode with Teflon cloth during EP
- "Degas" Nb in vacuum furnace at T > 600 °C





Q₀ Record



Figure 2 – Residual resistance as low as $0.5 \text{ n}\Omega$ is actually measured on large area cavities, giving an intrinsic quality factor Q₀ exceeding 2.10¹¹.







Multipacting





Multipacting

Multipacting is characterized by an exponential growth in the number of electrons in a cavity

Common problems of RF structures (Power couplers, NC cavities...)

Multipacting requires 2 conditions:

- Electron motion is periodic (resonance condition)
- Impact energy is such that secondary emission coefficient is >1





One-Point Multipacting



Resonance condition: Cavity frequency (ω_g) = n x cyclotron frequency $\omega_g = n\omega_c$ n: MP order

→ Possible MP barriers given by
$$H_n \propto \frac{m\omega_g}{n\mu_0 e}$$

The impact energy scales as $K \propto \frac{e^2 E_{\perp}^2}{2}$

+ SEY, $\delta(K)$, > 1 = MP

 $m\omega_g^2$

Empirical formula: H

$$H_n\left[\text{Oe}\right] = \frac{0.3}{n} f_0\left[\text{MHz}\right]$$







Two-Point Multipacting





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Two-Side Multipacting



Secondary Emission in Niobium







MP in SRF Cavities





"Near pill-box" shape

Early SRF cavity geometries (1960s-'70s) frequently limited by multipacting, usually at < 10 MV/m







MP in SRF Cavities







Cures for Multipacting



• Cavity design

- Lower SEY: clean vacuum systems (low partial pressure of hydrocarbons, hydrogen and water), Ar discharge
- RF Processing: lower SEY by e⁻ bombardment (minutes to several hours)





Recent Examples of Multipacting





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Field Emission

- Characterized by an exponential drop of the Q_0
- Associated with production of x-rays and emission of dark current





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SNS HTB 54 Radiation at top plate versus Eacc 5/16/08 cg



DC Field Emission from Ideal Surface

Fowler-Nordheim model



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Field Emission in RF Cavities



Acceleration of electrons drains cavity energy

Intensity of x-rays and field emission current is many orders of magnitude higher than predicted by FN theory...

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Impacting electrons produce:

- line heating detected by thermometry
- bremsstrahlung X rays



Foreign particulate found at emission site

$$J = \frac{k}{\Phi} \frac{1.54 \times 10^6 (\beta E)^{5/2}}{\Phi} e^{-6.83 \times 10^3 \Phi^{3/2} / \beta E}$$

 β : enhancement factor (10s to 100s) *k*: effective emitting surface





How to Investigate Field Emission





Dissection and analysis











Dissection and SEM









Example of Field Emitters



Stainless steel











DC Field Emission Microscope











Type of Emitters





•Tip-on-tip

model can explain why only 10% of particles are emitters for Epk < 200 MV/m.

Ni

V



Smooth nickel particles emit less

or emit at higher fields.









Tip-on-tip Model

- Smooth particles show little field emission
- Simple protrusions are not sufficient to explain the measured enhancement factors
- Possible explanation: tip-on-tip (compounded enhancement)







FE onset vs. Particulate Size









Enhancement by Absorbates

Adsorbed atoms on the surface can enhance the tunneling of electrons from the metal and increase field emission





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Intrinsic FE of Nb



Single-crystal Nb samples showed FE onset higher than 1 GV/m.

The work function was obtained from the I-V curves:

 $\Phi = 4.05 \pm 17\%$ eV for Nb (111) $\Phi = 3.76 \pm 27\%$ eV for Nb (100)





Cures for Field Emission

• **Prevention:**

- Semiconductor grade acids and solvents
- High-Pressure Rinsing with ultra-pure water
- Clean-room assembly
- Simplified procedures and components for assembly
- Clean vacuum systems (evacuation and venting without re-contamination)
- Post-processing:
 - Helium processing
 - High Peak Power (HPP) processing





Helium Processing

- Helium gas is introduced in the cavity at a pressure just below breakdown (~10⁻⁵ torr)
- Cavity is operating at the highest field possible (in heavy field emission regime)
- Duty cycle is adjusted to remain thermally stable
- Field emitted electrons ionized helium gas
- Helium ions stream back to emitting site
 - Cleans surface contamination
 - Sputters sharp protrusions





Helium Processing







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Helium Processing







Helium Processing in CEBAF

Improvement of Cavity Performance with Helium Processing

Distribution of Maximum Gradients by Type of Limitation







Helium Processing in CEBAF







Practical Limitations (CEBAF)











Power = 1.5 MW Pulse Length = 250 us





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local melting leads to formation of a plasma and finally to the explosion of the emitter \rightarrow "star bursts" caused by the plasma



















Issues with HPP



Fig. 2: Cavity C19 before and after HPP. The Q0 recovered partially after warm up to room temperature.

- Reduced Q₀ after processing
- No experience with HPP above E_{acc} = 30 MV/m in 9-cell cavities
- Very high power required





Thermal Breakdown (Quench)

Localized heating

Hot area increases with field

At a certain field there is a thermal runaway, the field collapses

- sometimes displays a oscillator behavior
- sometimes settles at a lower value
- sometimes displays a hysteretic behavior











Thermal Breakdown



Thermal breakdown occurs when the heat generated at the hot spot is larger than that can be transferred to the helium bath causing T > T_c : "quench" of the superconducting state







Quench Mechanism



Temperature difference between inner surface and helium bath temperature (two dimensional case):

- The RF current produces heat
- Superconductors are bad thermal conductors:
 - Thermal conductivity
 - Kapitza Nb/He interface resistance
- A small normalconducting defect can produce a very large heating (Factor 10⁶ surface resistance!)



High thermal and Kapitza conductivity required !!







Thermal Breakdown: Simple Model



The power dissipation (in watts) at the defect is

$$\dot{Q}_{\rm T}=\frac{1}{2}R_{\rm n}H^2\pi a^2. \label{eq:QT}$$

Heat flow out through a spherical surface:

$$-4\pi r^2 \kappa \frac{\partial T}{\partial r} = 2\dot{Q}_T$$

When the defect reaches T_c , the field reaches its maximum value

$$H_{
m max} = \sqrt{rac{4\kappa(T_c-T_b)}{aR_{
m n}}}.$$

Breakdown field given by (very approximately):

$$H_{tb} = \sqrt{\frac{4k_T(T_c - T_b)}{r_d R_d}}$$





Thermal Conductivity of Nb





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Numerical Thermal Model Calculations



Note: H_{tb} has nearly no dependence on $T_B < 2.1$ K





Magneto-thermal Breakdown

- Quench location identified by T-mapping
- Morphology of auench site reproduced by replica technique



Local Magnetic Field Enhancement: Quench when $\beta H > H_c$





Magneto-thermal Breakdown: Maximum E_{acc}



$$E_{acc}^{\max} = d \frac{r H_{c,RF}}{\beta_m \left(H_p / E_{acc} \right)}$$

 $r \le 1$, reduction of the local critical field within the penetration depth, due to impurities or lattice imperfection

- *d*, thermal stabilization parameter $\propto \sqrt{\kappa}$
- $\beta_m > 1$, geometric field enhancement factor







Type of Defects











Surface defects, holes can also cause TB

0.1 – 1 mm size defects cause TB







Optical Inspection

- long distance microscope (Cornell)
 - resolution: 12 µm/pixel (limited by camera)
- University Kyoto and KEK camera system
 - resolution: 7 µm/pixel
 - variable light system for height measurement







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-100



1000

1500

2000

500

Defects Seen by Optical Inspection

Cell 6, Quench at 16 MV/m on equator



- Auger analysis: no foreign material
- EDX analysis: increased content of carbon in black spots





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Defects Seen by Optical Inspection

Cell 5, Quench at 23 MV/m on equator





3D image, bump and hole up to 200 µm deep







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Cures for Quench

- Prevention: avoid the defects
 - High-quality Nb sheets
 - Eddy-current scanning of Nb sheets
 - Great care during cavity fabrication steps
- Post-treatment:
 - Thermally stabilize defects by increasing the RRR
 - Remove defects: local grinding





Post-purification for Higher RRR



- Post-purification by solid-state gettering
- use Ti (or Y) as getter material => higher affinity for O, (N, C) than Nb
 - coating of cups or cavity with getter material at 1350 C (Ti) under UHV
 - diffusion of O from Nb to Ti until equilibrium
- 1) Increase of RRR = 250-300 to RRR = 500 700
 2) Homogenizing impurities



Disadvantages:

- > 50 μ m material removal necessary after heat treatment
- Significant reduction of yield strength of the Nb







Post-purification





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Post-purification





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How High of RRR Value is Necessary?









Defect Repair: Local Grinding





Polymond + water for grinding Polymond: diamond particles in a resin (particle size = $40 \sim 3$ um)









Defect Repair: Local Grinding



Quench at E_{acc}=20 MV/m



Figure 1.) Q₀ vs E runs at 2.00K and 1.80K.





Summary on Quench

- Big improvement in Cavity fabrication and treatment less foreign materials found (at limitations <20MV/m only)
- Visual inspection systems are available
- Many irregularities in the cavity surface are found with this systems during and after fabrication and treatment pits and bumps
 - weld irregularities
- Often one defect limits the whole cavity
- Some correlations are found between defects and quench locations at higher fields

But often no correlation between suspicious pits and bumps and quench location

• At gradient limitations in the range >30 MV/m defects are often not identified





High-Field Q-Slope ("Q-drop")









Q-drop and Baking



- The origin of the Q-drop is still unclear. Occurs for all Nb material/treatment combinations
- The Q-drop recovers after UHV bake at 120 °C/48h for certain material/treatment combinations







Experimental Results on Q-drop



• "Hot-spots" in the equator area (high-magnetic field)







Experimental Results on Q-drop



• Q-drop and baking effect observed in both TM_{010} and TE_{011} modes. TE mode has no surface electric field

Q-drop: high magnetic field phenomenon

Onset of Q-drop is higher for

- smooth surfaces
- reduced number of grain boundaries



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Baking: Material and Preparation Dependence

Baking **works** on cavities made of:

• Large-grain Nb (buffered chemical polished or electropolished)



Smooth surface, few grain boundaries

50 µm

• Fine-grain Nb, electropolished



Smooth surface, many grain boundaries

• Fine-grain Nb, post-purified, BCP

Smooth surface, fewer grain boundaries

100 µm

Baking **does not work** on cavities made of:

• Fine-grain Nb, buffered chemical polished



100 μm



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Rough surface, many grain boundaries



Recipe against Q-drop

• Recipes necessary to overcome the Q-drop, depending on the starting material, based on current data:







Baking Effects on Low-field R_s and H_{c3}



- Decrease of R_{BCS} due to ↓ of *l* and ↑ of energy gap
- The physics of the niobium surface changes from CLEAN (l > 200 nm) to DIRTY LIMIT ($l \approx 25$ nm $\cong \xi_0$)

 $r_{32}=B_{c3}/B_{c2}$: depends on bake temperature and duration






Models of Q-drop & Baking

- Magnetic field enhancement
- Oxide losses
- Oxygen pollution
- Magnetic vortices





Magnetic Field Enhancement Model







AFM image of a grain boundary edge

Local quenches at sharp steps (grain boundaries) when $\beta_m H > H_c$

β_m : Field enhancement factor

 $\geq Q_0(B_p)$ calculated assuming

✓ Distribution function for β_m values

✓ The additional power dissipated by a quenched grain boundary is estimated to be ~ 17 W/m











The model cannot explain the following experimental results:

- Single-crystal cavities have Q-drop
- Seamless cavities have Q-drop
- Low-temperature baking does not change the surface roughness
- Electropolished cavities have Q-drop, in spite of smoother surface





Interface Tunnel Exchange Model



Band structure at Nb-NbO_x-Nb₂O_{5-y} interfaces



Schematic representation of the Nb surface



- Resonant energy absorption by quasiparticles in localized states in the oxide layer
- Driven by electric field $E_0 > \frac{\varepsilon_r \Delta}{\rho \beta^* \tau^*}$

$$R_{s}^{E} = b \left[\left(e^{-c/E_{p}} - e^{-c/E_{0}} \right) + \left(\frac{c}{E_{p}} e^{-c/E_{p}} - \frac{c}{E_{0}} e^{-c/E_{0}} \right) + \frac{1}{2} \left(\frac{c^{2}}{E_{p}^{2}} e^{-c/E_{p}} - \frac{c^{2}}{E_{0}^{2}} e^{-c/E_{0}} \right) \right]$$

J. Halbritter et al., IEEE Trans. Appl. Supercond. 11 (2001) p. 1864



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ITE Model: Shortcomings

The model cannot explain the following experimental results:

- The baking effect is stable after re-oxidation
- The Q-drop was observed in the TE_{011} mode (only magnetic field on the surface)
- The Q-drop is re-established in a baked cavity only after growing an oxide ~ 80 nm thick by anodization





Oxygen Pollution Model

- Surface analysis of Nb samples shows high concentrations of interstitial oxygen (up to ~ 10 at.%) at the Nb/oxide interface
- Interstitial oxygen reduces T_c and the H_{c1}

Magnetic vortices enter the surface at the reduced H_{c1} , their viscous motion dissipating energy

• The calculated O diffusion length at 120°C/48h is ~ 40 nm Interstitial oxygen is diluted during the 120°C

baking, restoring the H_{c1} value for pure Nb



Calculated oxygen concentration at the metal/oxide interface as a function of temperature after 48h baking

G. Ciovati, Appl. Phys. Lett. 89 (2006) 022507



After baking



Oxide cluster



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Oxygen Pollution Model: Shortcomings

The model cannot explain the following experimental results:

- The Q-drop did not improve after 400°C/2h "in-situ" baking, while O diffuses beyond λ
- The Q-drop was not restored in a baked cavity after additional baking in 1 atm of pure oxygen, while higher O concentration was established at the metal/oxide interface
- Surface analysis of single-crystal Nb samples by X-ray scattering revealed very limited O diffusion after baking at 145°C/5h





Fluxons as Source of Hot-Spots

- Motion of magnetic vortices, pinned in Nb during cool-down across T_{c} cause localized heating
- Periodic motion of vortices pushed in & out of the Nb surface by strong RF field also cause localized heating

The small, local heating due to vortex motion is amplified by R_{BCS} , causing cm-size hot-spots





Thermal Feedback with Hot-Spots Model



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The effect of "defects" with reduced superconducting parameters is included in the calculation of the cavity R_s

• This non-linear R_s is used in the heat balance equation

Hot-spots

$$u(\theta) = \theta e^{1-\theta}$$
$$\frac{2B_p^2}{B_{b0}^2} = 1 + g + u(\theta) - \sqrt{\left[1 + g + u(\theta)\right]^2 - 4u(\theta)}$$

$$Q_{0}(B_{p}) = \frac{Q_{0}(0)e^{-\theta}}{1 + g/\left[1 - (B_{p}/B_{b0})^{2}\right]}$$

Fit parameters:

g related to the No. and intensity of hot-spots

 $Q_0(0)$ low-field Q_0

 \mathbf{B}_{b0} quench field

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Q-drop: Recent Samples Results

Samples from regions of high and low RF losses were cut from single cell cavities and examined with a variety of surface analytical methods.

No differences were found in terms of:

- roughness
- oxide structure
- crystalline orientation





It was found that "hot-spot" samples have a higher density of crystal defects (i.e. vacancies, dislocations) than "cold" samples



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2°



